

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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C. Healion

Apple No. : 10/587,194 Confirmation No. 8444
Applicant : Jean-Louis Stehle
Filed : July 24, 2006
Title : PROTECTED PATTERN MASK FOR REFLECTION LITHOGRAPHY
IN THE EXTREME UV OR SOFT X-RAY RANGE
TC/A.U. : 1795
Examiner : Jonathan G. Jelsma
Docket No. : 58059/N75
Customer No. : 23363

AMENDMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450
Post Office Box 7068
Pasadena, CA 91109-7068
May 28, 2009

Commissioner:

In response to the Office action of November 28, 2009, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.